	Hits	Search Text	DBs
65	6	((EUV or UV or VUV or DUV or X$2ray) near9 (laser or ablat$4 or irradiat$4 or illuminat$4 or expos$4) near12 (resist or photoresist) near10 (remain$3 or residu$5) near19 strip$4 near12 (remov$5))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
66	18	((EUV or UV or VUV or DUV or X$2ray) near22 (laser or ablat$4 or irradiat$4 or illuminat$4 or expos$4) near12 (resist or photoresist) near10 (remain$3 or residu$5 or pattern) near29 strip$4 near29 (remov$5))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
67	6	((EUV or UV or VUV or DUV or X$2ray or ultraviolet) near22 (laser or ablat$4 or irradiat$4 or illuminat$4 or expos$4) near12 (resist or photoresist) near10 (pattern) near29 strip$4 near29 (remov$5)) and ((resist or photoresist) near12 (residu$3 or remain$4) near26 (UV or EUV or DUV or X$3ray or VUV or ultraviolet) near12 (irradait$4 or illuminat$4 or imping$4 or expos$4) near29 develop$4)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB